

Sheet 1 of 1  <b>Information Disclosur Citation</b>	Attorney Docket No. DP-302242 DIV	Serial No.
	Applicant: David Boyd Rich et al.	
	Filing Date	Group Art Unit:

U. S. Patent Documents						
Ref. Desig.	Examiner's Initials	Document Number	Date	Name	Class/ Subclass	(If appropriate) Filing Date
1.		5450751	9/19/95	Putty et al.	73/504.18	
2.		5547093	8/20/96	Sparks	216/2	
3.		5872313	2/16/99	Zarabadi et al.	73/497	
4.		6127273	10/3/00	Laermer et al.	438/709	
5.		6257062	7/10/01	Rich	73/514.32	
6.						
7.						
8.						
9.						

Foreign Patent Documents							
Ref. Desig.	Examiner's Initials	Document Number	Date	Country	Class/ Subclass	Translation	
						Yes	No
1.							
2.							
3.							

OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, etc.)		
Ref. Desig.	Examiner's Initials	
1.		Disclosed Anonymously, "High Etch and High Precision Silicon Etches for Micromachine Release," Research Disclosure, June 1999
2.		
3.		
4.		

Examiner:	Date Considered:
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